WHAT IS CLAIMED IS:

1. A positioning apparatus configured to move a movable part on a surface parallel to a first direction and a second direction perpendicular to each other, and comprising a single guide serving as a guide configured to constrain a position of the movable part in the second direction and a drive mechanism configured to drive the movable part,

wherein the movable part includes

a first movable member movable in the first direction while being guided by the guide,

a second movable member having a first end and a second end, the first end being connected to the first movable member via a rotation bearing and moving above the surface, and

a third movable member movable within a predetermined range between the first end and the second end while being guided by the second movable member,

the drive mechanism includes

a first driver configured to drive the first end of the second movable member in the first direction, and

a second driver configured to drive the second end of the second movable member in the first direction, and

the first driver includes a first stator and a first mover connected to the first end of the second movable member without interposing the rotation bearing.

2. The apparatus according to claim 1, wherein

the guide has a guide surface parallel to the first direction, the first movable member being guided by the guide

surface via a first static pressure bearing, and

the guide surface is arranged between the first stator and the first movable member.

3. The apparatus according to claim 2, further comprising a first linear encoder configured to measure a position of the first mover,

wherein the first linear encoder includes a detection head configured to move together with the first mover.

4. The apparatus according to any one of claims 1 to 3, wherein the second driver includes a second stator and a second mover configured to move together with the second movable member, and

a distance between the second stator and the second end of the second movable member changes in accordance with a pivot movement of the second movable member about a rotation axis of the rotation bearing.

5. The apparatus according to claim 4, further comprising a second linear encoder configured to measure a position of the second mover,

wherein the second linear encoder includes a detection head configured to move together with the second mover.

6. The apparatus according to any one of claims 1 to 5, wherein the second movable member is guided by the surface via a second static pressure bearing.

7. The apparatus according to any one of claims 1 to 6, wherein the third movable member is guided by the surface via a third static pressure bearing.

8. The apparatus according to any one of claims 1 to 6, wherein the third movable member is guided by the surface via third and fourth static pressure bearings which are arranged along the first direction, and a central portion of the third movable member is arranged between the third static pressure bearing and the fourth static pressure bearing.

9. The apparatus according to claim 2 or 3, wherein the guide surface is perpendicular to the surface.

10. The apparatus according to claim 2, wherein a height of a fixing member between the first movable member and the rotation bearing with reference to the surface is between respective heights of a lower end and an upper end of the first static pressure bearing with reference to the surface.

11. The apparatus according to any one of claims 2, 3, and 9, wherein the surface is formed by an upper surface of a base plate, and the guide surface is formed by a side surface of the base plate.

12. A lithography apparatus comprising:

a positioning apparatus defined in any one of claims 1 to 11; and

a substrate chuck mounted on the third movable member of the positioning apparatus so as to being positioned above the second movable member,

wherein the lithography apparatus is configured to transfer an original pattern to a substrate held by the substrate chuck.

13. The lithography apparatus according to claim 12, wherein

the lithography apparatus is configured as one of an imprint apparatus and an exposure apparatus.

14. A method of manufacturing an article, comprising:

transferring a pattern to a substrate by using a lithography apparatus defined in claim 12 or 13; and

processing the substrate to which the pattern has been transferred to obtain the article.